

BRAZILIAN MEETING ON ORGANIC SYNTHESIS BENTO GONÇALVES, RS - BRAZIL

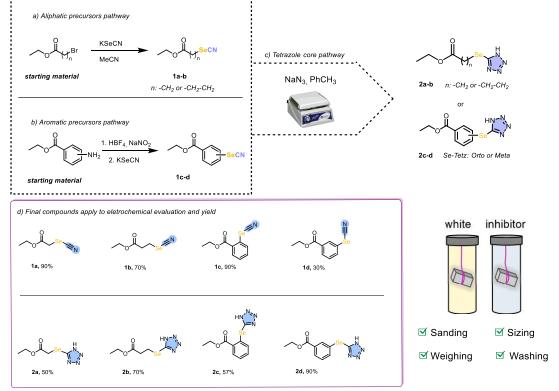
## Synthesis and Characterization of Highly Efficient Anticorrosive Organoselenium Derivatives Containing 1H-Tetrazole Nucleus

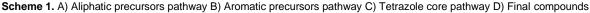
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Keywords: Anticorrosive, Selenium, Tetrazole.

## ABSTRACT

Corrosion is the spontaneous degradation of metallic materials due to environmental interaction. One main protection method for metal alloys is using organic corrosion inhibitors<sup>1</sup>. Compounds with heteroatoms (N, O, S) and  $\pi$  electrons enhance adsorbent properties on metal surfaces by donating electron pairs to empty d orbitals, forming protective layers<sup>1</sup>. Also, organoselenium<sup>2</sup> compounds are promising anticorrosives due to their strong bond formation with metals.ref Thus, this work aims to synthesize and evaluate organoselenium 1H-tetrazole derivatives to evaluate the anticorrosive effects The precursors **1a-d** (SeCN) were synthesized by combining the portion "SeCN" to the aliphatic (Scheme 1a) and aromatic (Scheme 1b) classes. The protocol used was based in two different methods: an SN2 reaction with bromides for aliphatic compounds and diazonium salt formation for aromatic compounds. The tetrazole<sup>3</sup> nucleus formation (Scheme 1c) was consistent for all SeCN precursors. By this way was possible to achieve **4** SeCN molecules and **4** tetrazole derivatives in excellent yields ranging from 30 to 90%. All these molecules were evaluated as anticorrosive and shown very good results, specially **2a** derivative that demonstrated being the best one.





ACKNOWLEDGEMENTS
UFF, FAPERJ, CAPES, CNPq
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